

Evaluation of analytical instrumentation

Part XXIV. Instrumentation for quadrupole inductively coupled plasma mass spectrometry

Received 14th June 2010, Accepted 14th June 2010

DOI: 10.1039/c005443g

A. C. ... C. ...
I. ... C. ... -C. ...

Introduction

A. C. ... C. ...
C. B. ... J. H. ... K. E. J. ... G. L. ...
E. J. ...
K. E. J. ...
C. ... -C. ...
A. ...
I. ...
C. ... -C. ...

... H ...
...
C ... 1. ...
C ... 2. ...
C ... 3. ...

Notes on the use of this document

...
...
...

... f(3) = f(2) + f(1) = 1 + 1 = 2
f(4) = f(3) + f(2) = 2 + 1 = 3

(C d.)

Instrument	Material	Area	Concentration
AA	L ¹ μ L ¹
F	μ L ¹

*b : L¹ ¼ 1 k.f. 10¹², L¹ ¼ 1 k.f. 10⁹, μ L¹ ¼ 1 k.f. 10⁶.

Instrument	Material	Area	Concentration
F

Instrument	Material	Area	Concentration
(a) Previous instruments			
() I	C	I	IC
()	C	I	
()	F	I	
()	H	I	
() C	C	I	
(b) Servicing			
()	A	I	E
() A		I	
() E		I	A
(c) Technical support			
() A		I	
()			
()		I	
()		I	A
()			

(C 4)

F. 1	b f	I 1
I 1		
1. High frequency (HF) generators	<p>27 H</p>	A.
(a) 1	H	HF
(b) 1	A.	I

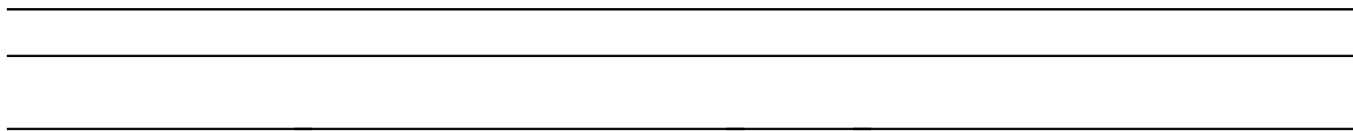
(C 4)

.....

F. f I f f

C f f f f f f f f f

(



(C 4)

.....

F. f I f f

() C I 7

..... C

.....

(C 4d)

.....

F. f I f f

8. Instrument control and monitoring

(a) I f f
.....
.....
.....

(C d.)

